

**(b.) Amendments to the Claims**

Kindly delete claims 1, 2 and 3 in entirety and substitute therefore new claims 4, 5 and 6 as follows:

Claims 1 -3 (canceled).

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Claim <sup>b</sup>~~4~~ (new).

In a plasma film-forming apparatus which includes a film-forming chamber in which a substrate is arranged, a film-forming gas introducing pipe connected to a supply source of a film-forming gas at a first end thereof, a shower plate having numerous holes and interposed between a second end of said film-forming gas introducing pipe and said film-forming chamber, film-gas exciting means for exciting film-forming gas introduced through said numerous holes of said shower plate into said film-forming chamber to form a film on the surface of said substrate with a chemical reaction, radicals-producing means which excites a cleaning gas and produces radicals, and cleaning-gas introducing means for introducing said cleaning gas containing said free radicals into said film-forming chamber, said cleaning-gas introducing means communicating directly with said film forming chamber without passing through said shower plate.

Claim <sup>7</sup>~~5~~ (new).

A plasma film-forming apparatus according to claim 4, in which said cleaning-gas introducing means comprises a first cleaning-gas introducing pipe, communicating with said film-forming chamber from one of two opposite walls of said chamber, and a second cleaning-gas introducing pipe communicating with said film-forming chamber from

the other of the opposite walls, and said first and second cleaning-gas introducing pipes are offset from the centers of said walls in opposite directions.

B/t

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Claim ~~8~~ (new).

A plasma film-forming apparatus according to claim 4 or 5 in which the inside surface of said cleaning-gas introducing means is coated with polytetra fluoro ethylene.

